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11/15/2010

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: Miwa KOZAWA et al. Art Unit: 1795

Application Number: 10/720,097 Examiner: Daborah Chacko Davis

Filed: November 25, 2003 Confirmation Number: 4454

For: PROCESS FOR FORMING RESIST PATTERN, SEMICONDUCTOR DEVICE

AND FABRICATION THEREOF

Attorney Docket Number: 032132 Customer Number: 38834

RESPONSE UNDER 37 C.F.R. §1.116 EXPEDITED PROCESSING REQUESTED

MAIL STOP AF Commissioner for Patents October 29, 2010

P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

In response to the Office Action dated August 4, 2010, Applicant amends the claims as follows and submits the following remarks.

Amendments to the Claims begin on page 2 of this paper.

Remarks/Arguments begin on page 7 of this paper.